



*Workshop on “Heusler Alloys for Spintronic Devices”  
July 30, 2015 @C-SPIN, Univ. of Minnesota, Minneapolis, USA*

# ***CPP-GMR and Related Phenomena in Half-Metallic Heusler Alloy Systems***

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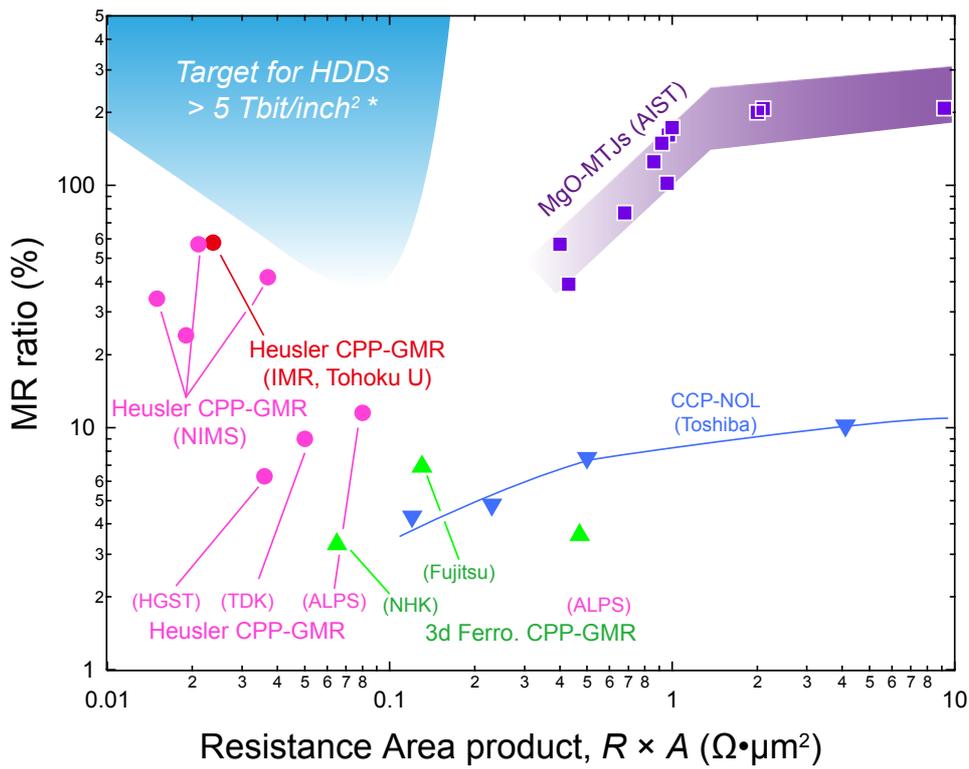
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## **Research activities on Heusler alloys in my group**

- ***CPP-GMR*** with  $\text{Co}_2\text{Fe}_{1-x}\text{Mn}_x\text{Si}$  electrodes
- ***Spin torque oscillation*** with CPP-GMR devices
- ***Giant Peltier effect*** in CPP-GMR devices
- ***Perpendicular magnetization*** of  
Heusler alloy thin films
- ***Antiferromagnetic*** Heusler alloy films  
to replace IrMn in spin valves

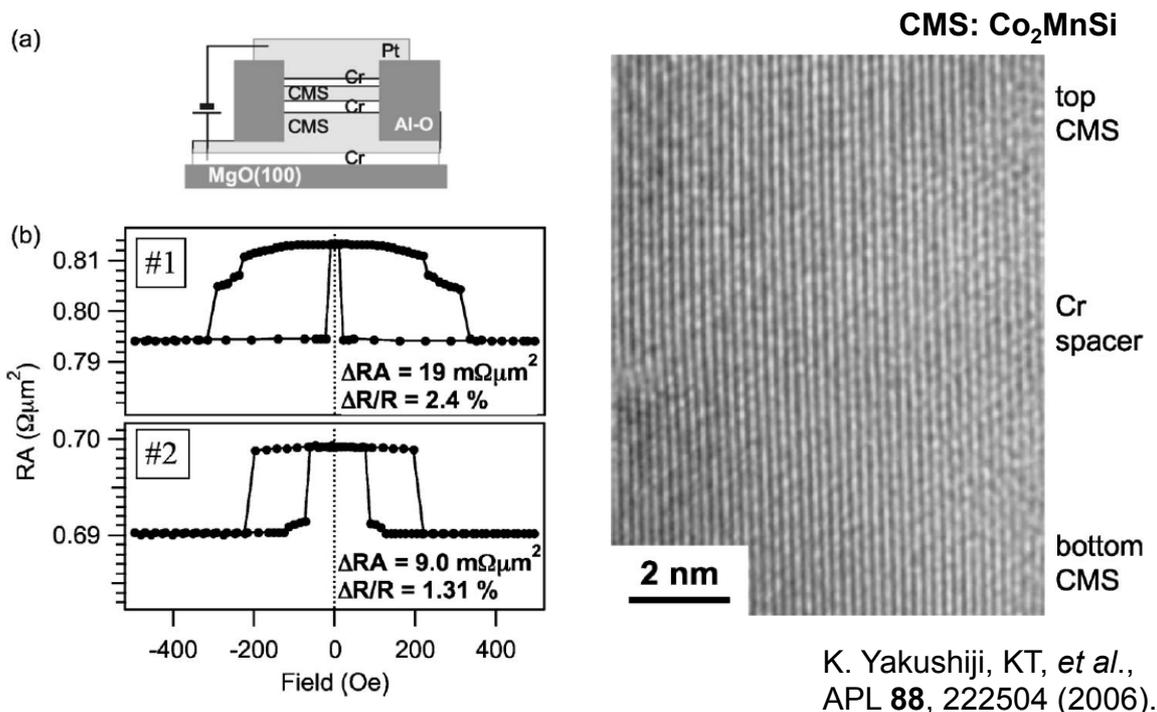
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# High MR ratio with low resistance



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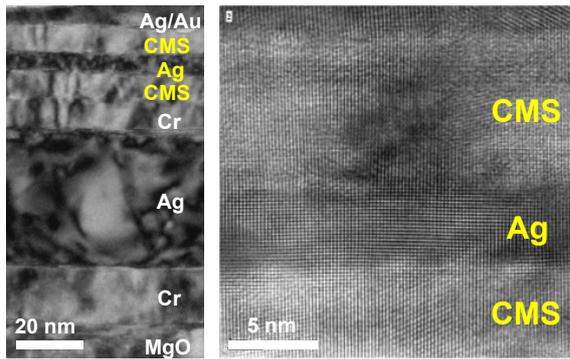
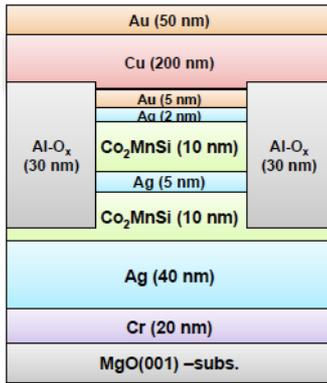
## CMS/Cr/CMS fully-epitaxial CPP-GMR device



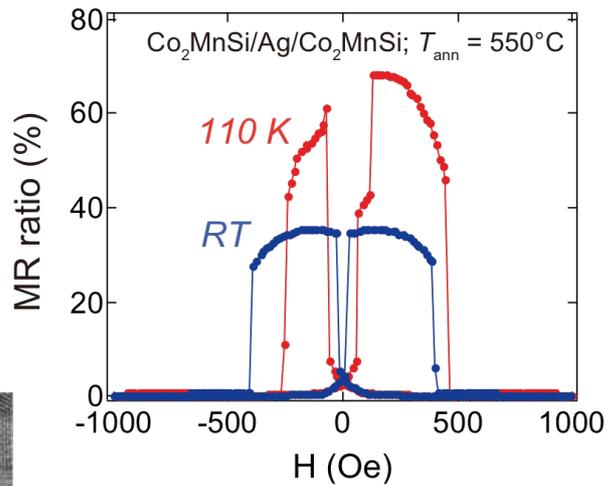
The first experimental report on Heusler-based CPP-GMR devices with large  $\Delta RA$  values.

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# CMS/Ag/CMS fully-epitaxial CPP-GMR device



Fully-epitaxial growth in CMS/Ag/CMS



**Breakthrough of CPP-GMR**

A high MR ratio (**36.4%@RT**) was observed.

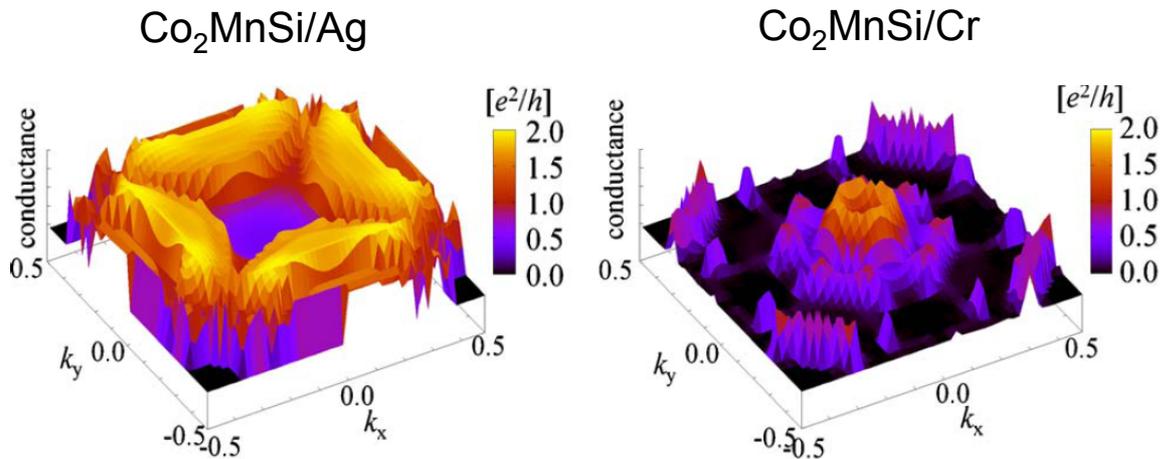
T. Iwase, KT *et al.*, Appl. Phys. Exp., 2 (2009) 063003.  
Y. Sakuraba, KT *et al.*, Phys. Rev. B82 (2010) 094444.

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## Ag spacer? or Cr spacer?

Majority spin conductance in the parallel state

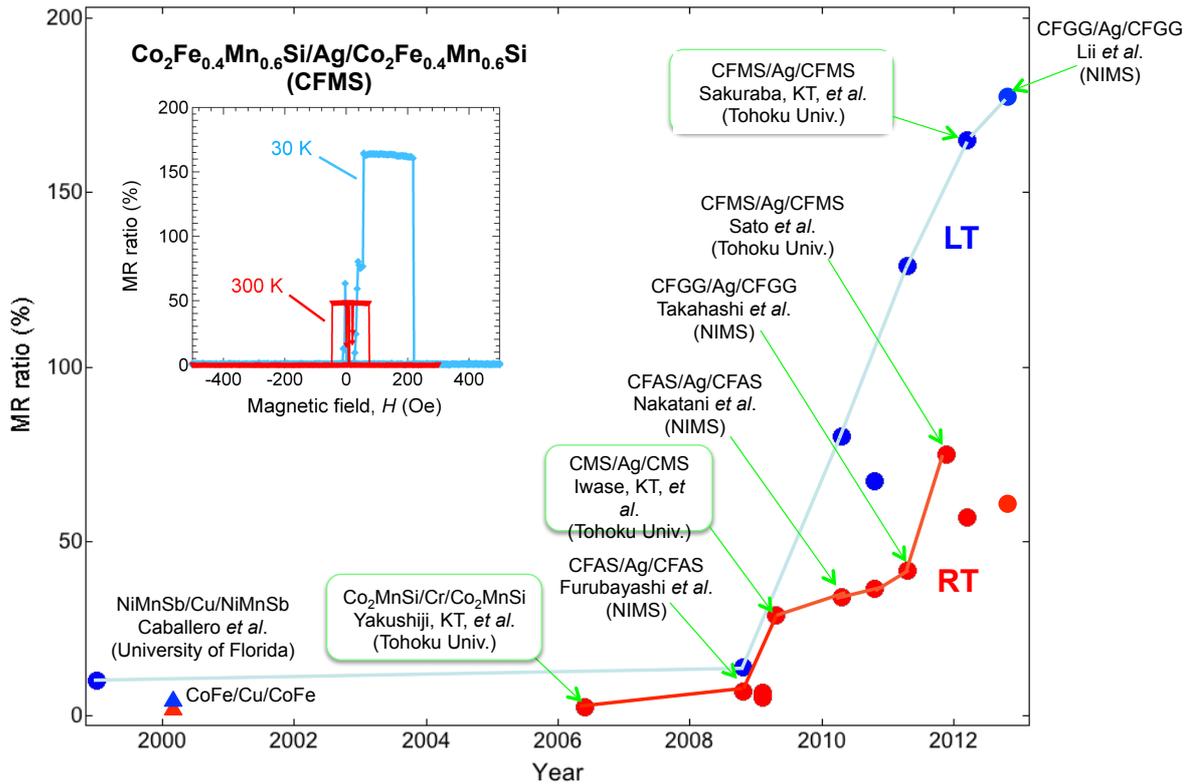
Sakuraba, Miura, KT, *et al.*,  
PRB **82**, 094444 (2010).



Matching of the Fermi surface is important.

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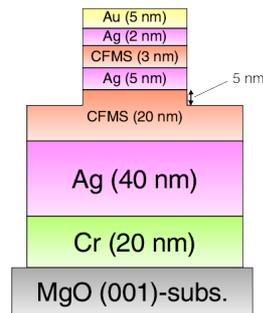
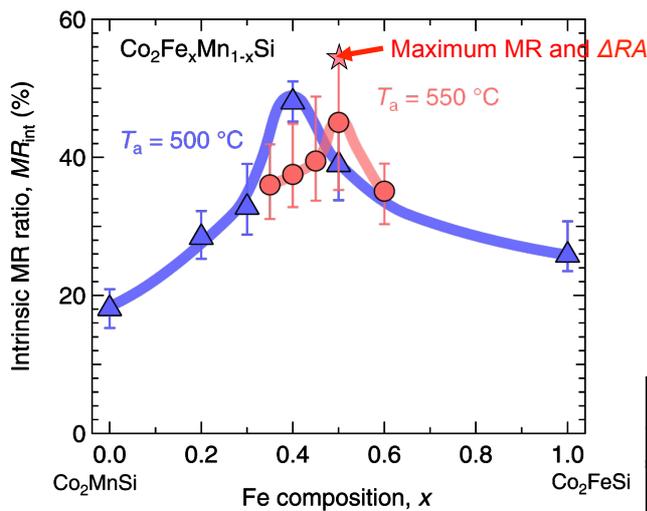
# Development of CPP-GMR for Heusler alloys



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## CPP-GMR with Co<sub>2</sub>Fe<sub>x</sub>Mn<sub>1-x</sub>Si electrodes

Fe:Mn composition ratio x dependence



$T_a$	$x_{best}$	$MR_{int}$	RA	$\Delta RA$
500	0.4	51 %	25.1 m $\Omega \cdot \mu m^2$	12.8 m $\Omega \cdot \mu m^2$
550	0.5	55 %	31.4 m $\Omega \cdot \mu m^2$	17.2 m $\Omega \cdot \mu m^2$

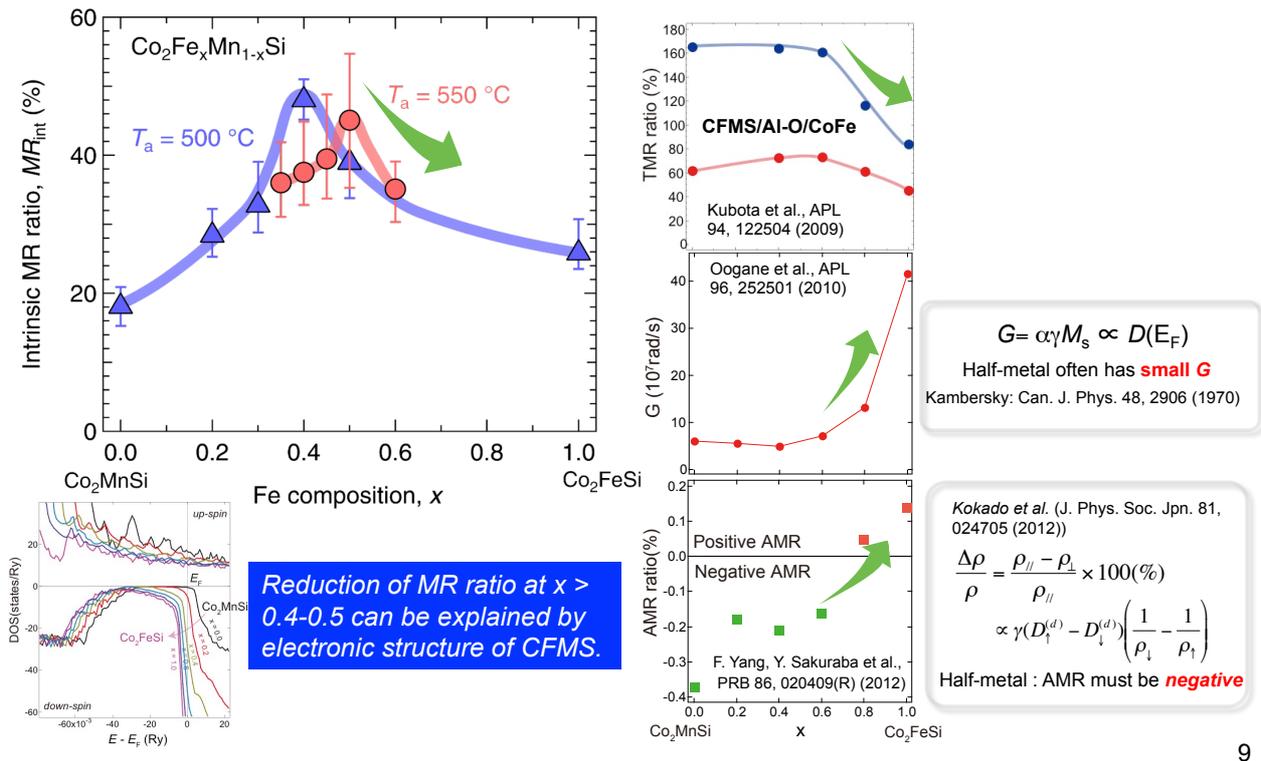
Y. Sakuraba, M. Ueda et al. Appl. Phys. Lett. **101**, 252408(2012).

- The best composition  $x = 0.4$  at  $T_a = 500^\circ C$   
0.5 at  $T_a = 550^\circ C$
- The highest  $\Delta RA$  of 17.2 m $\Omega \cdot \mu m^2$  was observed in Co<sub>2</sub>Fe<sub>0.5</sub>Mn<sub>0.5</sub>Si.

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# CPP-GMR with $\text{Co}_2\text{Fe}_x\text{Mn}_{1-x}\text{Si}$ electrodes

Discussion - Fe:Mn composition ratio  $x$  dependence ( $x > 0.4-0.5$ )

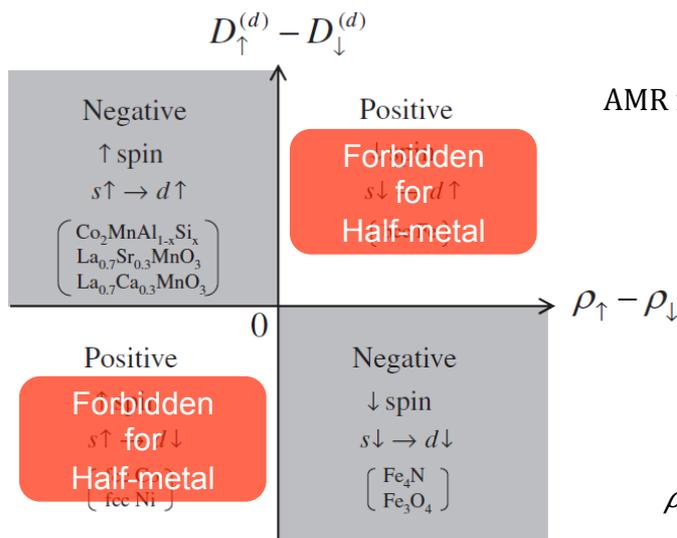


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## Half-metallic materials & AMR effect

s-d scattering procedures and the sign of AMR ratio

S. Kokado, et al., JPSJ 81, 024705 (2012).



$$\text{AMR ratio} \equiv \Delta\rho/\rho$$

$$= \gamma(\rho_{\downarrow}s_{\downarrow} \rightarrow d_{\uparrow} - \rho_{\uparrow}s_{\downarrow} \rightarrow d_{\downarrow}) / \rho_{\uparrow\downarrow} + \rho_{\downarrow\uparrow}$$

$$\propto \gamma(D_{\uparrow}^{(d)} \uparrow\uparrow - D_{\downarrow}^{(d)} \downarrow\downarrow) (1/\rho_{\uparrow\downarrow})$$

with

$$\rho_{\downarrow\sigma} = \rho_{\downarrow}s_{\downarrow}\sigma + \rho_{\downarrow}s_{\uparrow}\sigma \rightarrow d_{\sigma}$$

$$\gamma = (3/4)(\lambda/H_{\text{ex}}) \uparrow^2$$

$\rho_{\downarrow\sigma}$ : Resistivity of  $\sigma$  spin

$D_{\uparrow}^{(d)}$ : Density of states of  $d$ -electron

$\lambda$ : Spin-orbit coupling constant

$H_{\text{ex}}$ : exchange field of the  $d$ -states

Half-metallic materials

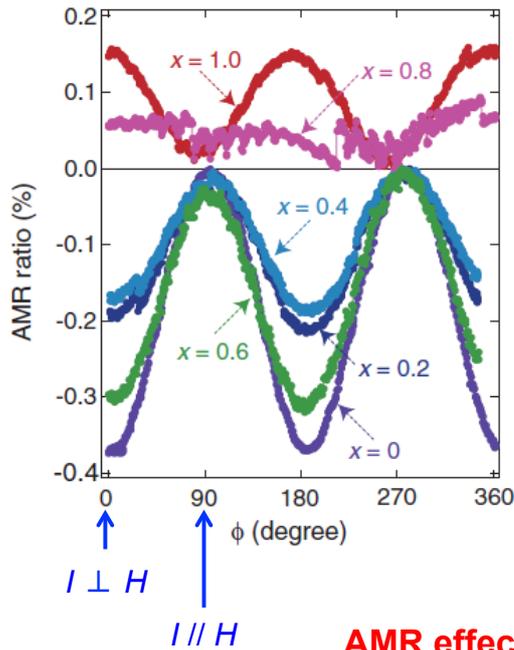


Negative sign of AMR ratio

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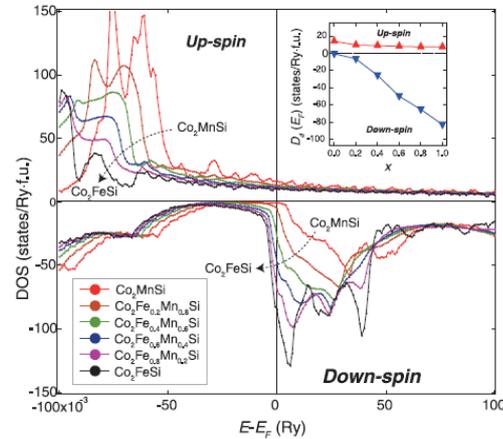
# AMR effects of Heusler alloy films

AMR curves of  $\text{Co}_2\text{Fe}_x\text{Mn}_{1-x}\text{Si}$  films



Yang, Sakuraba, KT, *et al.*, PRB **86**, 020409(R) (2012).

DOS of  $\text{Co}_2\text{Fe}_x\text{Mn}_{1-x}\text{Si}$  alloys (calc.)

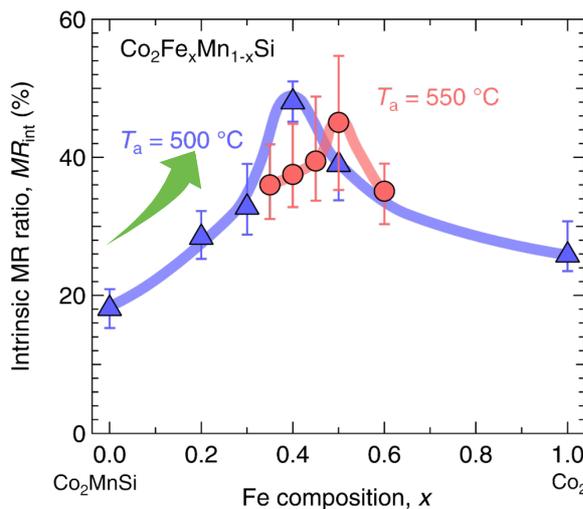


AMR effect is a fingerprint for half-metallicity.

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## CPP-GMR with $\text{Co}_2\text{Fe}_x\text{Mn}_{1-x}\text{Si}$ electrodes

Discussion - Fe:Mn composition ratio  $x$  dependence



Calculated exchange stiffness by first-principles calculations (Dr. Miura, Tohoku univ.)

Exchange stiffness of Co [meV]	$\text{Co}_2\text{MnSi}/\text{Ag}$	$\text{Co}_2\text{FeSi}/\text{Ag}$
Interface	137	340 (x 2.5)
Bulk	414	536

bulk spin-asymmetry interface spin-asymmetry

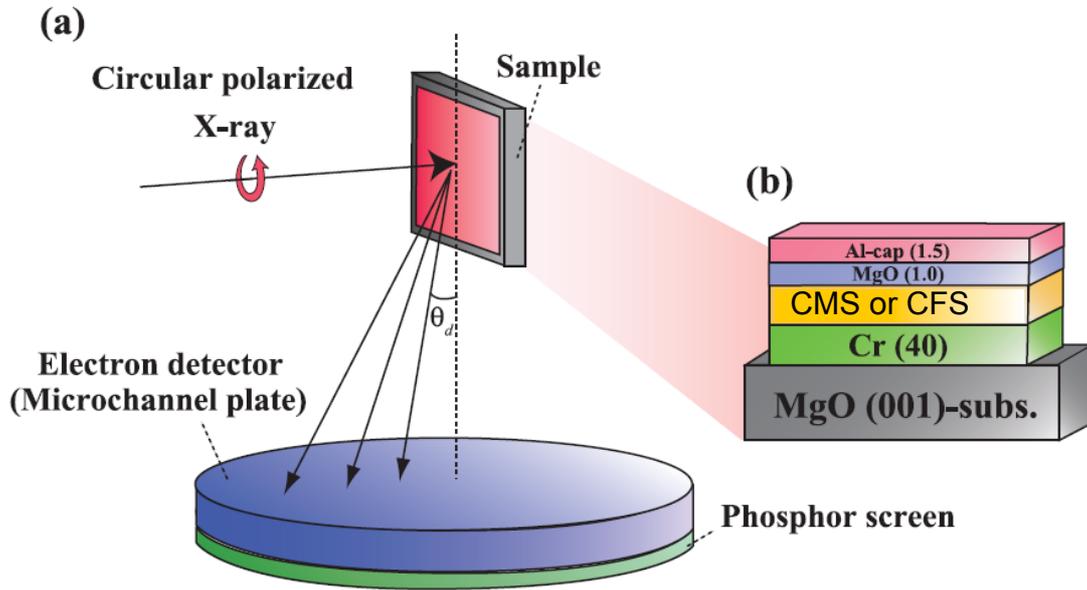
$$\Delta RA \propto \left( \underbrace{\beta \rho_{CFMS}^* t_{CFMS}}_{\text{bulk contribution}} + \underbrace{\gamma R_{CFMS/Ag}^* A}_{\text{Interface contribution}} \right)^2$$

Systematic analysis of  $\gamma$  is necessary to clarify the improvement of interfacial exchange stiffness.

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# Depth-resolved XMCD measurements

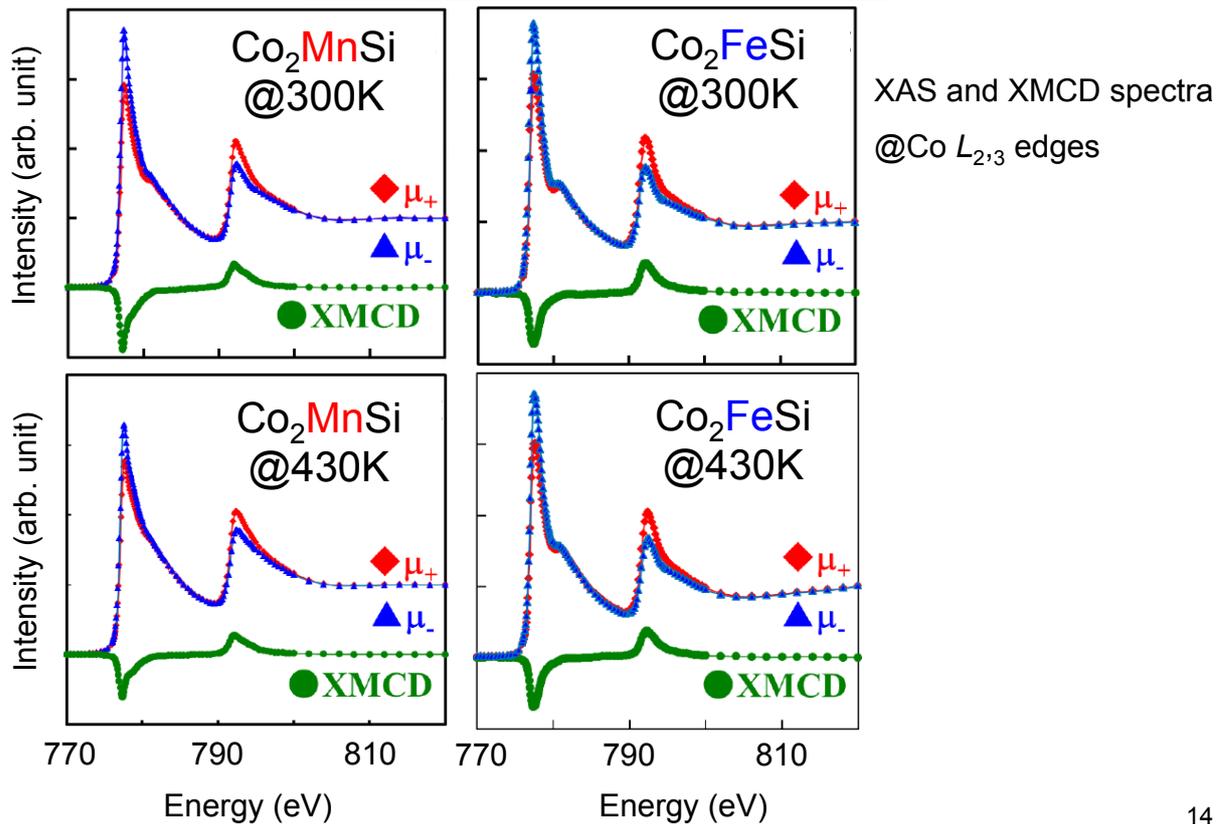
Measured@BL-16A, Photon Factory, KEK  
 Collaboration with Prof. Amemiya, Dr. Sakamaki



Soft x-ray  $\rightarrow$  penetration depth ( $\sim 5$  nm or less)  
 Depth-dependence of magnetic moments can be measured.

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# Exchange stiffness constants at interfaces



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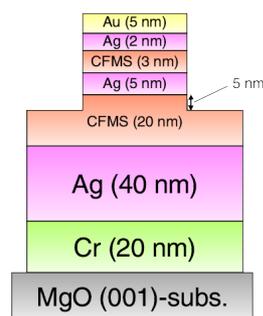
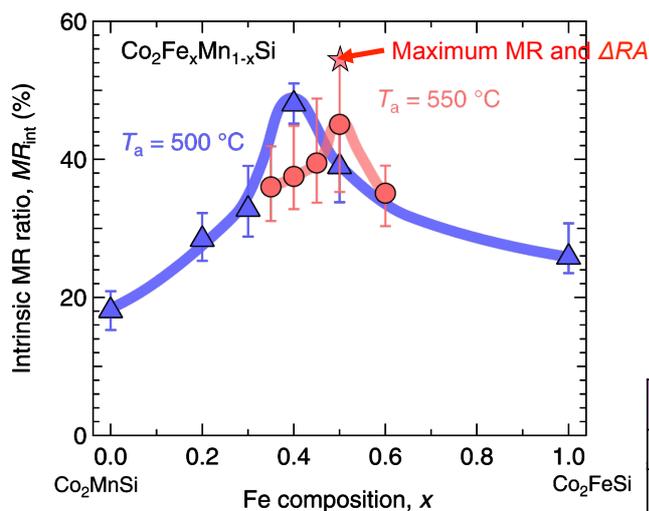
# “Bulk” moment & “Interface” moment

Temperature dependence of Co-moment at the interface;  
Larger for the  $\text{Co}_2\text{MnSi}/\text{Ag}$  case than that for the  $\text{Co}_2\text{FeSi}/\text{Ag}$  case

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## CPP-GMR with $\text{Co}_2\text{Fe}_x\text{Mn}_{1-x}\text{Si}$ electrodes

Fe:Mn composition ratio  $x$  dependence



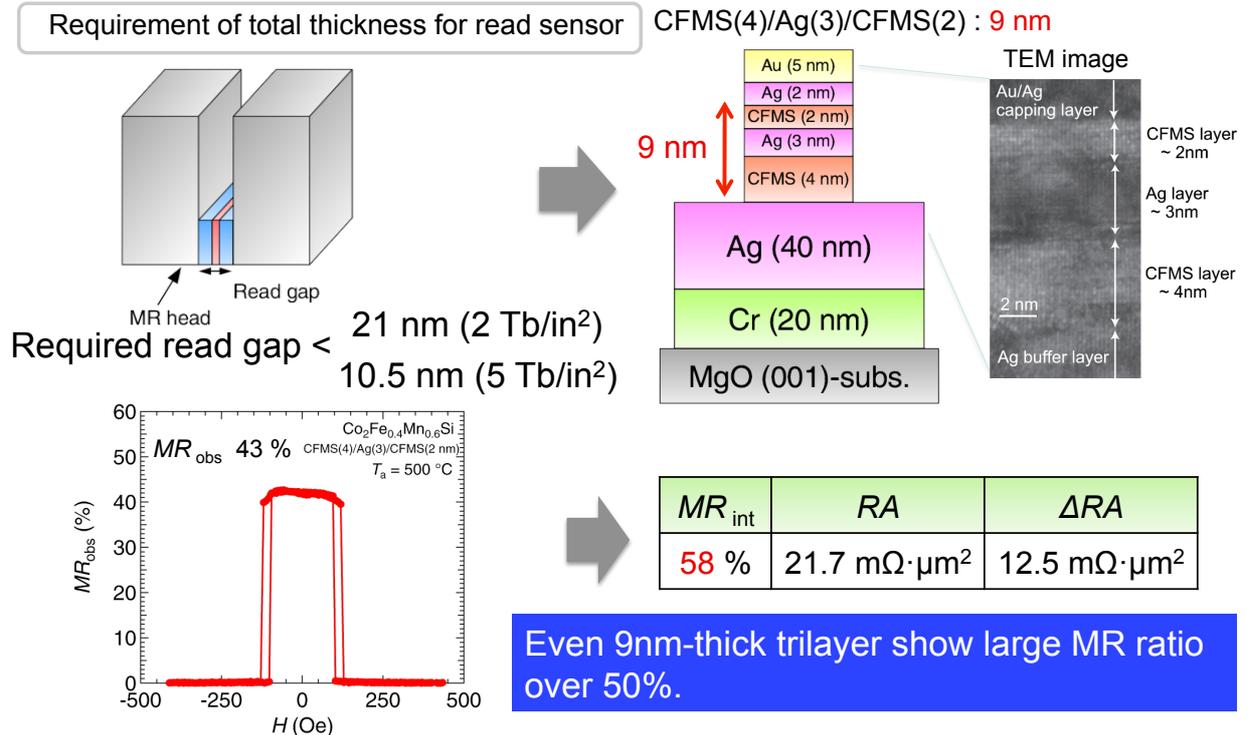
$T_a$	$x_{\text{best}}$	$MR_{\text{int}}$	$RA$	$\Delta RA$
500	0.4	51 %	$25.1 \text{ m}\Omega \cdot \mu\text{m}^2$	$12.8 \text{ m}\Omega \cdot \mu\text{m}^2$
550	0.5	55 %	$31.4 \text{ m}\Omega \cdot \mu\text{m}^2$	$17.2 \text{ m}\Omega \cdot \mu\text{m}^2$

Y. Sakuraba, M. Ueda *et al.* Appl. Phys. Lett. **101**, 252408(2012).

$x = 0 \rightarrow 0.5$  : Interface contribution increases  $\rightarrow$  MR increases.  
 $x = 0.5 \rightarrow 1$  : Half-metallicity disappears  $\rightarrow$  MR decreases.

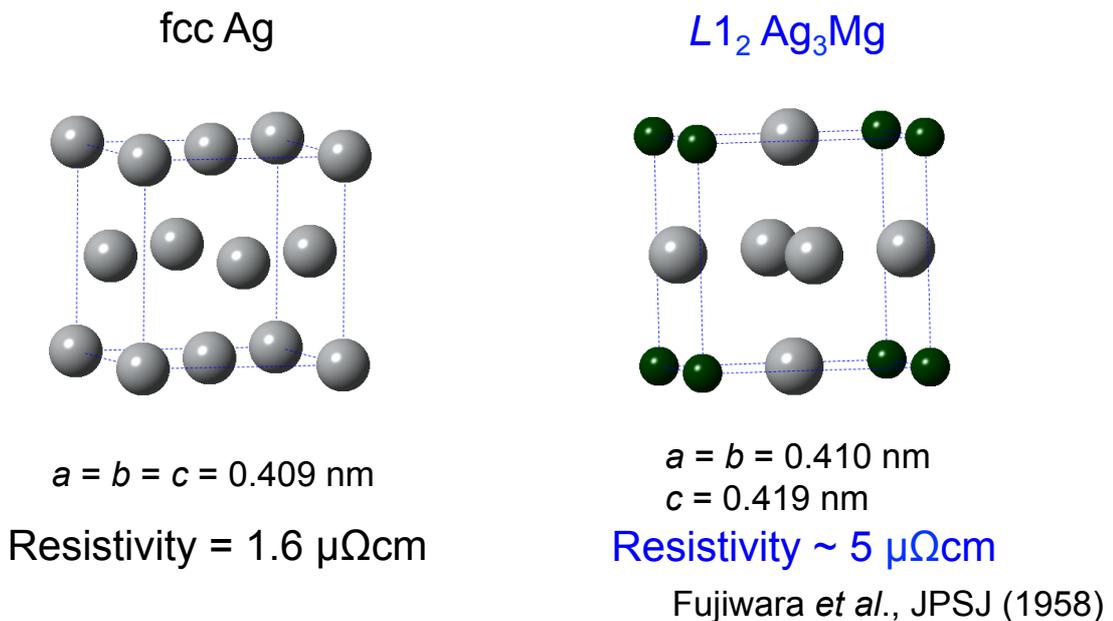
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# Challenge for a thinner layer thickness



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## Approach for higher output –new spacer material–

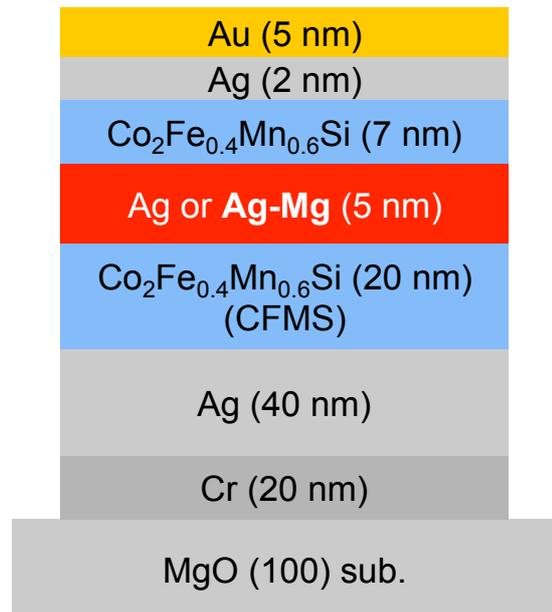


Lattice mismatch is similar (Ag ~ 2%,  $L1_2 \text{Ag}_3\text{Mg}$  ~ 3%).

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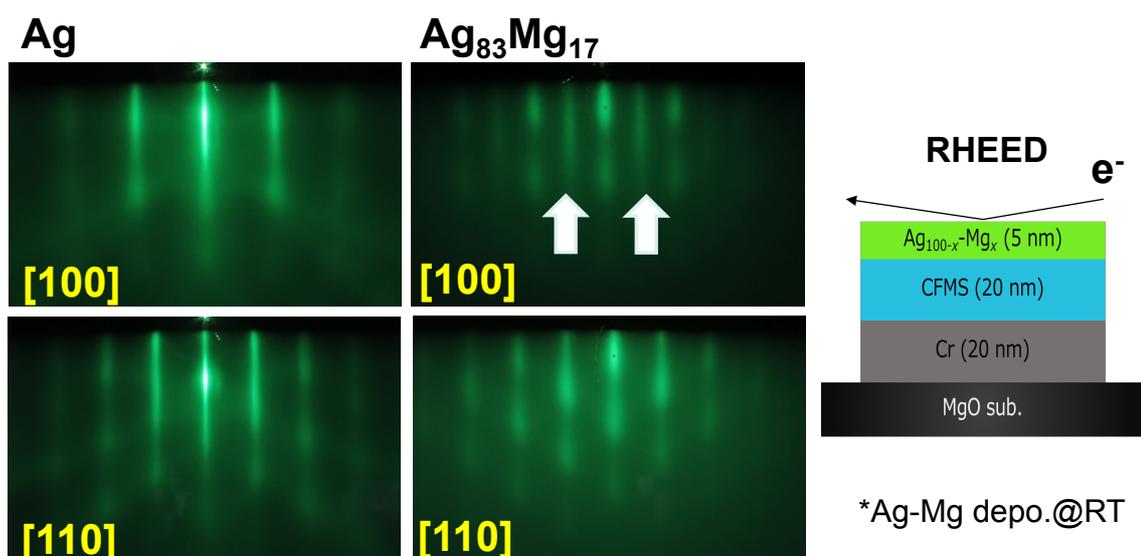
## Experimental procedures

- Film deposition: Magnetron sputtering
- *In situ* annealing
  - @650°C after the Cr depo.
  - @500°C after the top CFMS depo.
- Ag-Mg layer
  - Deposited by co-sputtering
- Fabrication of CPP-pillar:
  - Electron-beam lithography & Ar ion dry etching
- Characterization:
  - XRD, RHEED,
  - Direct-current 4-probe measurement



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## RHEED patterns of a thin Ag-Mg film

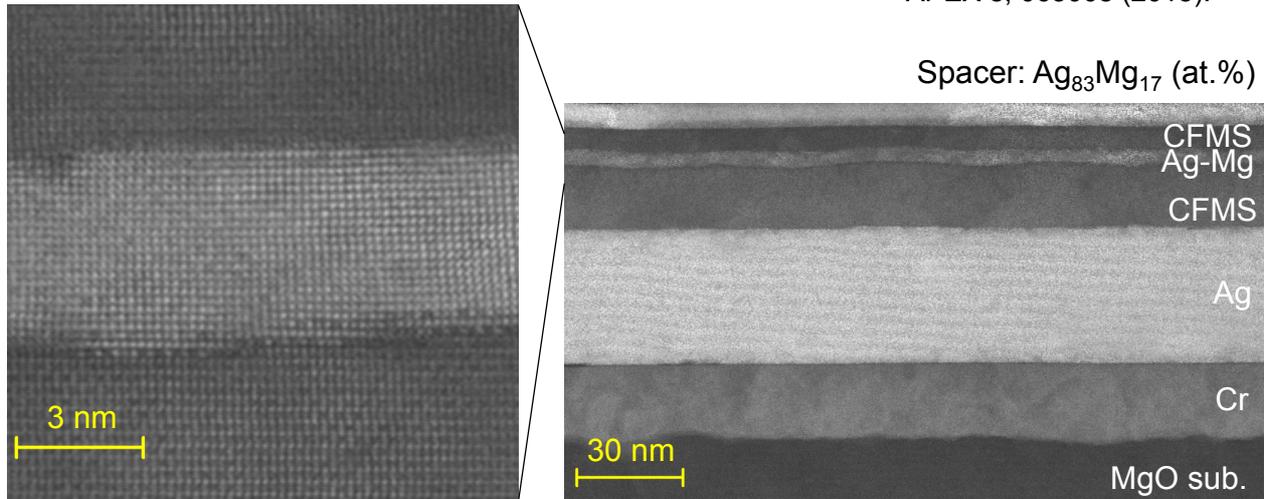


Superlattice diffraction was observed for the surface of Ag<sub>83</sub>Mg<sub>17</sub> (~ Ag<sub>5</sub>Mg) layer deposited at room temperature

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## Cross-sectional HAADF-STEM for Ag-Mg spacer

H. Narisawa, T. Kubota, KT, APEX 8, 063008 (2015).

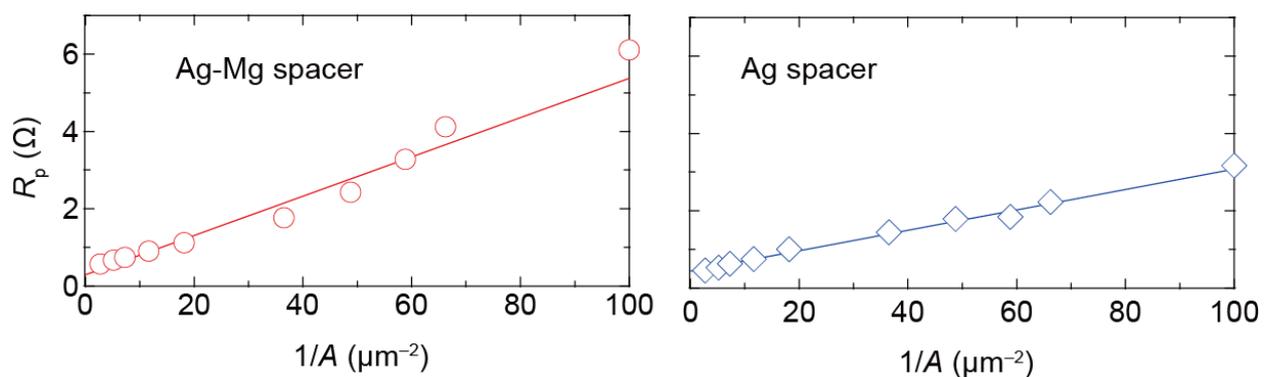


CFMS/Ag-Mg/CFMS → Flat and sharp interfaces

$\text{Ag}_{83}\text{Mg}_{17}$  spacer layer → Ordered locally at interfaces

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## RA in CFMS/Ag/CFMS



$$RA = 51 \pm 4 \text{ m}\Omega\mu\text{m}^2$$

$$R_{\text{para}} = 0.30 \pm 0.14 \Omega$$

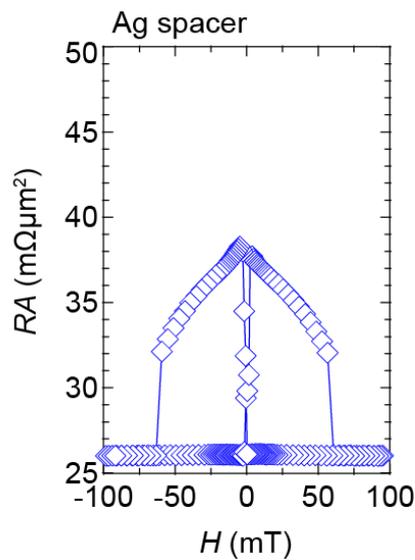
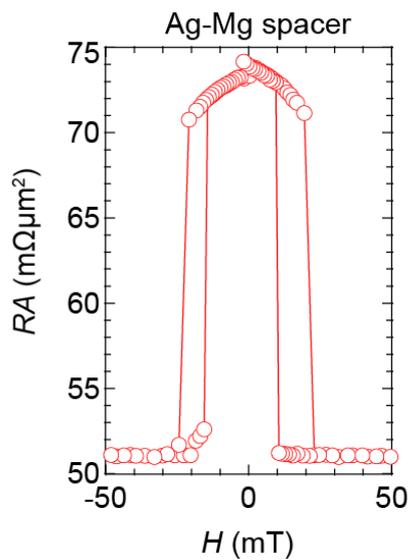
$$RA = 26 \pm 1 \text{ m}\Omega\mu\text{m}^2$$

$$R_{\text{para}} = 0.43 \pm 0.04 \Omega$$

RA for Ag-Mg spacer is twice larger than that for pure Ag spacer.

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## CPP-GMR in CFMS/Ag-Mg/CFMS



Large  $\Delta RA$  for Ag-Mg compared to that for Ag

$$*MR_{int} = \Delta R / (R_p - R_{para})$$

Spacer	RA (mΩμm <sup>2</sup> )	MR <sub>obs</sub> (%)	MR <sub>int</sub> (%)	ΔRA (mΩμm <sup>2</sup> )
Ag	26	35 (38)	48 (54)	13 (15)
L1 <sub>2</sub> Ag-Mg	51	36 (40)	44 (48)	<b>23 (25)</b>

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## Temperature dependence of CPP-GMR

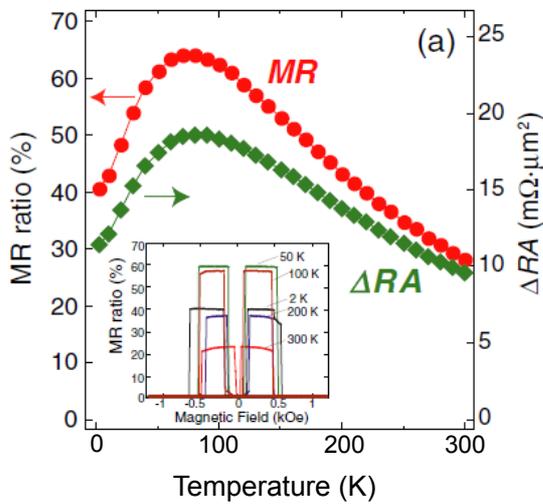
Ag spacer  
→ Maximum ~80 K

Ag-Mg spacer  
→ Maximum disappears.

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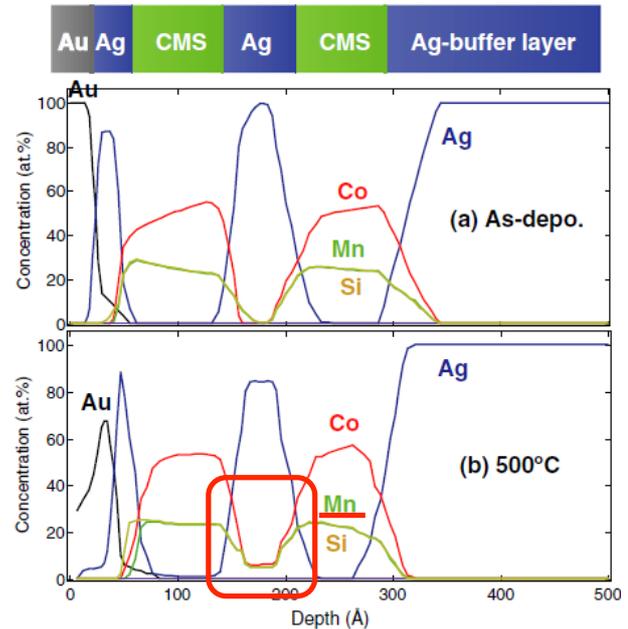
## Temp. dependence; effect of Mn-diffusion

Previous work on  
 $\text{Co}_2\text{MnSi}/\text{Ag}/\text{Co}_2\text{MnSi}$



Diffusion of Mn probably causes a maximum of the temp. dependence.

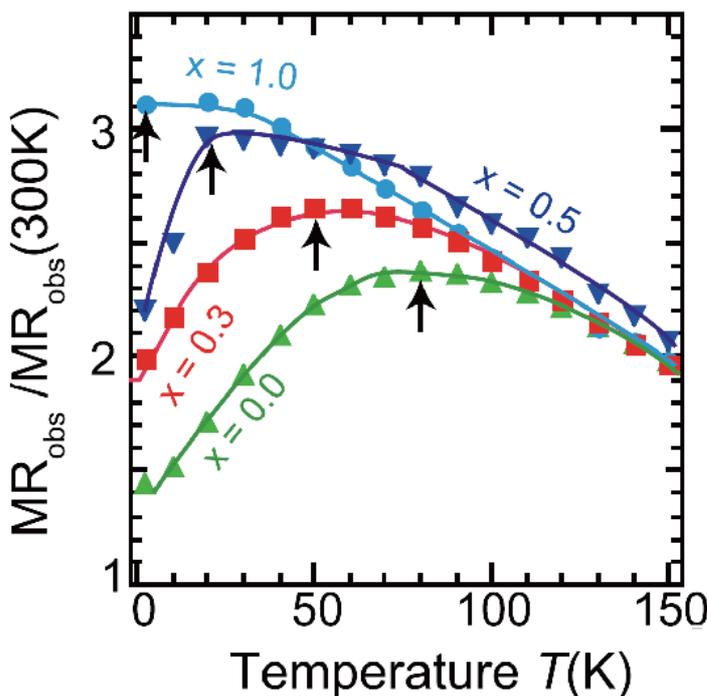
Depth profiles of the film composition (RBS)



Y. Sakuraba, *et al.*, J. Phys. D. (2011).

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## Temperature dependence of CPP-GMR



$\text{Co}_2\text{Fe}_x\text{Mn}_{1-x}\text{Si}$

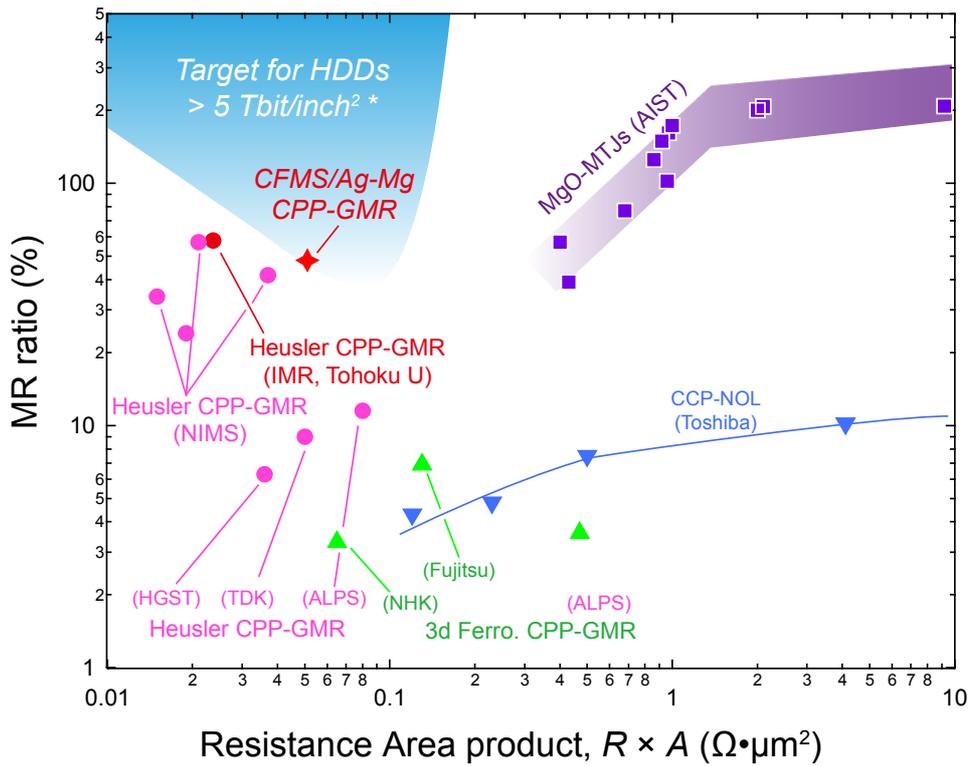
Y. Sakuaba, KT, *et al.*,  
Appl. Phys. Lett. **101**, 252408 (2012).

**Related to Kondo physics?**

L. O'Brien *et al.*,  
Nature Commun., 5:3927 (2014).

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# High MR ratio with low resistance

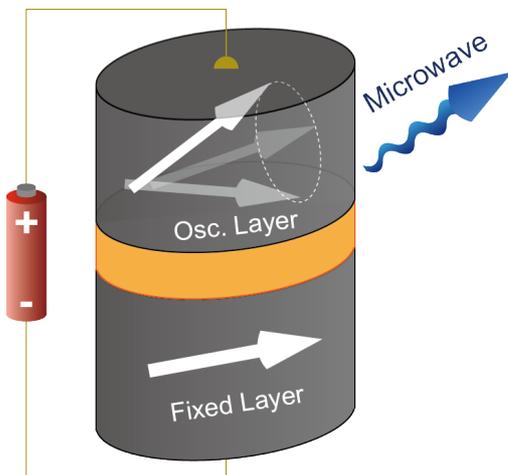


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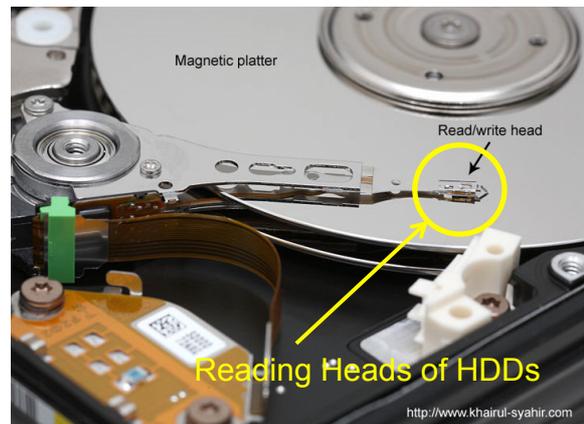
## Device applications using CPP-GMR devices

### Heusler-alloy-based CPP-GMR devices

Spin torque oscillators



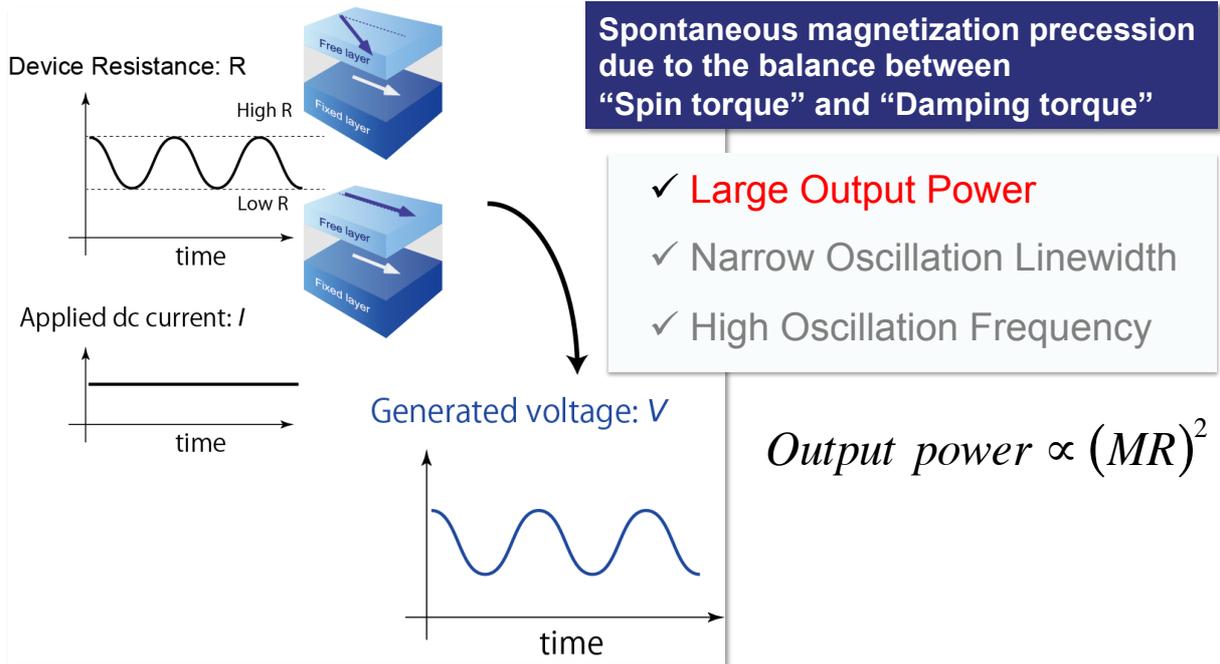
Read Heads in HDDs



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# Spin torque oscillator (STO)

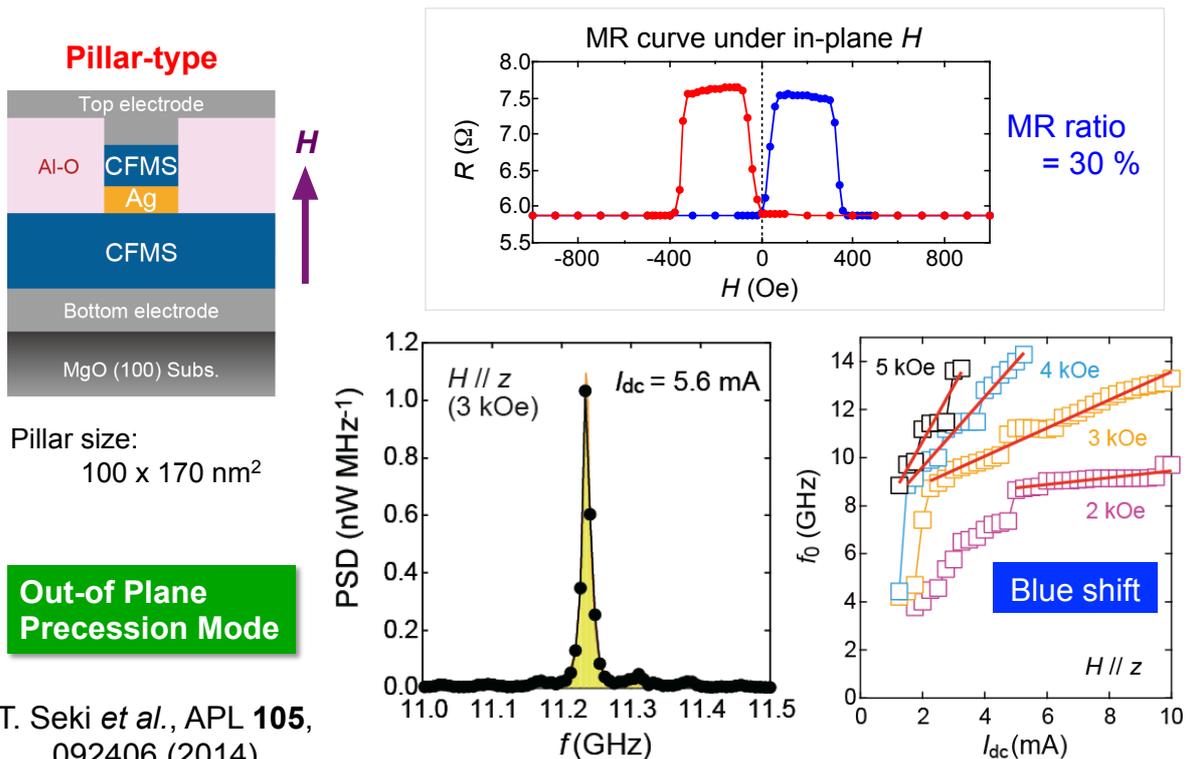
## What is Spin Torque Oscillation?



## Half-metallic Heusler alloy showing large MR

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## Heusler CPP-GMR STO (Pillar)



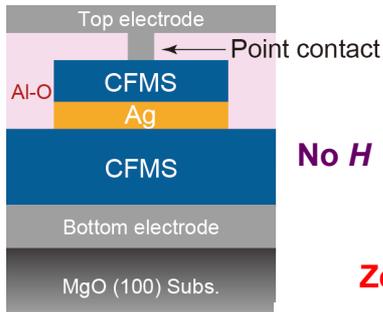
T. Seki *et al.*, APL **105**, 092406 (2014)

$P_{out} = 23.7\ nW, Q = 1124$

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# Heusler CPP-GMR STO (Point Contact)

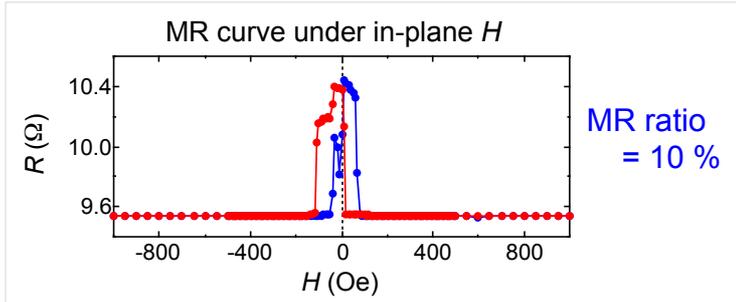
## Point Contact-type



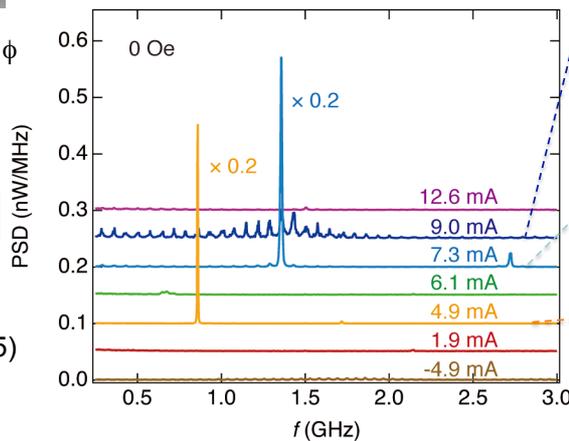
Contact size: 140 nm  $\phi$

Vortex-like Mode

T. Yamamoto *et al.*,  
APL **106**, 092406 (2015)



## Zero-field spin torque oscillation



**Region III: Incoherent**  
Multiple peak structure  
Chaotic dynamics?

**Region II: Coherent**  
 $f_0 = 1.36$  GHz  
 $\Delta f = 9$  MHz

**Region I: Coherent**  
 $f_0 = 0.86$  GHz  
 $\Delta f = 3$  MHz

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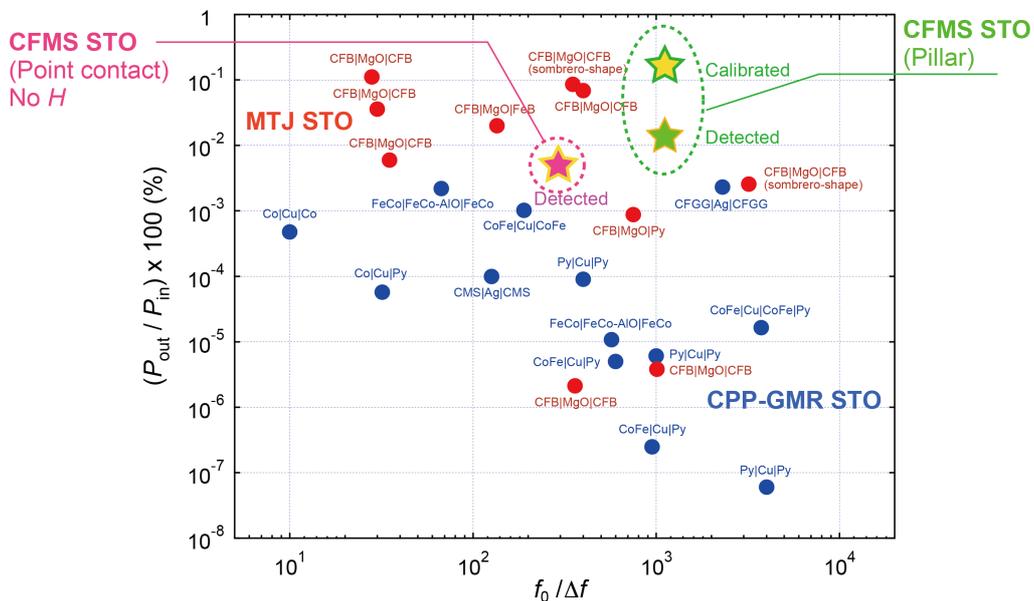
# Heusler CPP-GMR STO

Nanopillar	$P_{out} = 23.7$ nW	$\Delta f = 10$ MHz	$H = 3$ kOe ( $\parallel z$ )
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T. Seki *et al.*, APL **105**, 092406 (2014)

Point Contact	$P_{out} = 11.6$ nW	$\Delta f = 3$ MHz	$H = 0$ Oe
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T. Yamamoto *et al.*, APL **106**, 092406 (2015)



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# Summary

## Half-metallic Heusler alloys for spintronics

- **CPP-GMR in  $\text{Co}_2\text{Fe}_x\text{Mn}_{1-x}\text{Si}/\text{Ag}/\text{Co}_2\text{Fe}_x\text{Mn}_{1-x}\text{Si}$** 
  - **Composition dependence:**  
Max. of CPP-GMR @  $x=0.4\sim 0.5$
  - **Spacer: Ag  $\rightarrow$  Ag-Mg**  
Enhancement of  $\Delta RA$
  - **Temperature dependence of CPP-GMR**  
Maximum for CMS/Ag/CMS, CFMS/Ag/CFMS  
No Maximum for CFS/Ag/CFS, CFMS/Ag-Mg/CFMS
- **STO with CPP-GMR devices with CFMS/Ag/CFMS**
  - nanopillar-type; high output power and high Q
  - point contact-type; high output power and high Q with no applied field

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## Magnetic Materials Laboratory

### Lab members

Professor Koki Takanashi

Assoc. Prof. Masaki Mizuguchi

Assist. Prof. Takeshi Seki

Takahide Kubota

Post-doc. Zenchao Wen

Hitomi Yako

DC students Wei-Nan Zhou (China)

Jinhyeok Kim (Korea)

Takayuki Tashiro, Tatsuya Yamamoto, Tomoki Tsuchiya

MC students Junpei Shimada, Mingling Sun (China)

Yusuke Ina, Satoru Kikushima, Hidenobu Suzuki,



### Collaborators on Heusler work

Tomoko Sugiyama (IMR, Tohoku Univ.)

Yuya Sakuraba, Subrojati Bosu (NIMS, Tsukuba)

Masafumi Shirai (RIEC, Tohoku Univ.), Yoshio Miura (Kyoto Institute of Technology)

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